

**ABSTRACT**

An apparatus including:

(a) a substrate including a deposition region and an optional uncoated region, wherein the deposition region includes a level intermediate region disposed between a first end region and a second end region,

wherein the first end region includes a first raised surface portion extending above the level intermediate region and extending circumferentially around the first end region in a continuous manner; and

(b) a dip coated layer over the entire deposition region.